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FILING DATE FIRST NAMED INVENTOR ATTORNEY DOCKET NO. APPLICATION NO. 09/089.666 06/03/98 YAMAMOTO 149733/97 **EXAMINER** MMC1/0525 YOUNG & THOMPSON J. WINDAHA PAPER NUMBER 745 SOUTH 23RD STREET SUITE 200 ARLINGTON VA 22202 DATE MALED:

05/25/00

Please find below and/or attached an Office communication concerning this application or proceeding.

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UNITED STATES DEPARTMENT OF COMMERCE Patent and Trademark Office

NOTICE OF ALLOWANCE AND ISSUE FEE DUE

MMC1/0525

YOUNG & THOMPSON
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ARLINGTON VA 22202

APPLICATION NO. **TOTAL CLAIMS** FILING DATE **EXAMINER AND GROUP ART UNIT** DATE MAILED 09/089,666 06/03/98 021HACK, J 05/25/00 2812 First Named YAMAMOTO. 35 USC 154(b) term ext. = 0 Davs. Applicant

TITLE OF INVENTION

METHOD OF FABRICATING SEMICONDUCTOR DEVICE FOR PREVENTING RISING-UP OF SILISIDE

ATTY'S DOCKET NO.	CLASS-SUBCLASS	BATCH NO.	APPLN	l. TYPE	SMALL	ENTITY	, FEE DUE	DATE DUE
0 149733/9	7 438-	514 000	N06	UTIL	ťΥ	NO	\$1210.0	00 08/25/00

THE APPLICATION IDENTIFIED ABOVE HAS BEEN EXAMINED AND IS ALLOWED FOR ISSUANCE AS A PATENT. PROSECUTION ON THE MERITS IS CLOSED.

THE ISSUE FEE MUST BE PAID WITHIN <u>THREE MONTHS</u> FROM THE MAILING DATE OF THIS NOTICE OR THIS APPLICATION SHALL BE REGARDED AS ABANDONED. THIS STATUTORY PERIOD CANNOT BE EXTENDED.

HOW TO RESPOND TO THIS NOTICE:

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- II. Part B-Issue Fee Transmittal should be completed and returned to the Patent and Trademark Office (PTO) with your ISSUE FEE. Even if the ISSUE FEE has already been paid by charge to deposit account, Part B Issue Fee Transmittal should be completed and returned. If you are charging the ISSUE FEE to your deposit account, section "4b" of Part B-Issue Fee Transmittal should be completed and an extra copy of the form should be submitted.
- III. All communications regarding this application must give application number and batch number.

 Please direct all communications prior to issuance to Box ISSUE FEE unless advised to the contrary.

IMPORTANT REMINDER: Utility patents issuing on applications filed on or after Dec. 12, 1980 may require payment of maintenance fees. It is patentee's responsibility to ensure timely payment of maintenance fees when due.

C.	Application No.	Applicant(s)					
	09/089,666	YAMAMOTO, YOSHIAKI					
Notice of Allowability	Examiner	Art Unit					
	Jonathan Hack	2812					
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance and Issue Fee Due or other appropriate communication will be mailed in due course.							
 This communication is responsive to paper #8. The allowed claim(s) is/are 21-41. The drawings filed on 28 March 2000 are acceptable. Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d). All b)							
6. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient. A SUBSTITUTE OATH OR DECLARATION IS REQUIRED.							
 7. Applicant MUST submit NEW FORMAL DRAWINGS (a) because the originally filed drawings were declared by applicant to be informal. (b) including changes required by the Notice of Draftsperson's Patent Drawing Review(PTO-948) attached 1) hereto or 2) to Paper No. (c) including changes required by the proposed drawing correction filed, which has been approved by the examiner. (d) including changes required by the attached Examiner's Amendment / Comment. 							
Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the reverse side of the drawings. The drawings should be filed as a separate paper with a transmittal letter addressed to the Official Draftsperson.							
8. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.							
Any reply to this letter should include, in the upper right hand corner, the APPLICATION NUMBER (SERIES CODE / SERIAL NUMBER). If applicant has received a Notice of Allowance and Issue Fee Due, the ISSUE BATCH NUMBER and DATE of the NOTICE OF ALLOWANCE should also be included.							
Attachment(s)							
 1⊠ Notice of References Cited (PTO-892) 3□ Notice of Draftperson's Patent Drawing Review (PTO-948) 5□ Information Disclosure Statements (PTO-1449), Paper No 7□ Examiner's Comment Regarding Requirement for Deposit of Biological Material 	4∏ Interview Sui 6∏ Examiner's A	ormal Patent Application (PTO-152) nmary (PTO-413), Paper No mendment/Comment tatement of Reasons for Allowance					

Application/Control Number: 09/089,666

Art Unit: 2812

DETAILED ACTION

Allowable Subject Matter

1. Claims 21-41 are allowed.

The following is an examiner's statement of reasons for allowance: the prior art either singly or in combination fails to anticipate or render obvious the limitation heat treating to decrease a fluorine concentration to less than 1 x 10²⁰ atoms/cm², then forming a metal silicide layer. The prior art of Chiang et al US Patent 5,707,896 discloses a similar step of outgassing fluorine. Both the instant invention and Chiang et al implant BF₂ at similar energies, 30 KeV and 50-90 KeV respectively. Also, both implant similar dosages, 3 E15 and 1 E15 – 1 E16 respectively. Further, both outgass fluorine at similar temperatures, 700 C and 750-900 C respectively and for similar times 60 min and 20 to 60 min respectively. Chiang et al states that the "annealing is conducted at a temperature and time sufficient to outgas completely the fluorine atoms" (see column 5, lines 59-60). Chiang et al outgasses the fluorine to prevent delamination of an interlayer dielectric (ILD) layer resulting from voids formed from out-diffusion of the fluorine from a polysilicon surface during subsequent thermal processing in the presence of the ILD layer (see column 5, lines 40-48).

On the other hand, the instant invention outgasses fluorine to eliminate short circuits between the gate electrode and diffusion layers, and between diffusion layers due to the "rising up" reaction of a silicide formed during metallization (see paper #8, page 14). It is a close call as to whether or not the "rising up" reaction of a silicide would inherently be prevented from the process detailed by Chiang et al. All the process steps are essentially the same. In either case,

Page 3

the outgassing is performed prior to the deposition of the ILD or the silicide layer. Because of this, there would be essentially no detrimental fluorine left that could form voids or that could cause the "rising up". However, as Chiang et al does not discuss the problem of "rising up" nor the solution as discovered by Applicant, the Examiner is marginally persuaded that it would not have been obvious to one of ordinary skill to recognize that the solution to the problem of "rising up" would have been solved by outgassing as described by Chiang et al. See, In re Robertson, 169 F.3d 743, 745, 49 USPQ2d 1949, 1950-51 (Fed Cir. 1999).

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for

Allowance."

May 24, 2000

Supervisory Patent Examiner **Technology Center 2800**